CLAIMS

 A field effect transistor comprising at least a substrate, an organic semiconductor layer, an insulating layer, and a conductive layer, wherein

the insulating layer comprises a cured product of a phenol resin represented by a following general formula (1):

(wherein, R¹, R² and R³ are each independently at least one selected from the group consisting of hydrogen atom, halogen atom, hydroxymethyl group, alkyl group having 1 to 12 carbon atoms, alkenyl group, alkinyl group, alkoxyl group, alkylthio group, and alkyl ester group, X¹ and X² are each independently at least one selected from the group consisting of hydrogen atom, alkyl group having 1 to 12 carbon atoms, alkenyl group, alkinyl group, and aryl group, and n is an integer of 0 to 2,000.)

The field effect transistor according to
 claim 1, wherein the conductive layer comprises a gate electrode, a source electrode, and a drain electrode, the insulating layer includes a gate

insulating layer, and the gate insulating layer is a cured product of a phenol resin represented by the above general formula (1).

- 3. The field effect transistor according to claim 2, wherein the thickness of the gate insulating layer is 100 nm to 1 μm .
- The field effect transistor according to any one of claims 1 to 3, wherein part or all of the conducive layer comprises an agglomerate of
 conductive fine particles having a primary particle diameter of 5 nm to 2 μm.
- 5. A process for producing a field effect transistor comprising a substrate, an organic semiconductor layer, an insulating layer, and a conductive layer, the process comprising the steps of:

coating a thermosetting resin composition containing at least a phenol resin represented by the following general formula (1):

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(wherein, R^1 , R^2 and R^3 are each independently at

least one selected from the group consisting of hydrogen atom, halogen atom, hydroxymethyl group, alkyl group having 1 to 12 carbon atoms, alkenyl group, alkinyl group, alkoxyl group, alkylthio group, and alkyl ester group, X¹ and X² are each independently at least one selected from the group consisting of hydrogen atom, alkyl group having 1 to 12 carbon atoms, alkenyl group, alkinyl group, and aryl group, and n is an integer of 0 to 2,000.) and heating it to form the insulating layer.

6. The process for producing a field effect transistor according to claim 5, wherein part or all of the conductive layer is formed by applying a solution, dispersion, or paste of a conductive material or a precursor of the conductive material and heating it.

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7. The process for producing a field effect transistor according to claim 5, wherein the softening point of the phenol resin contained in the thermosetting resin composition is in the range of 70 to 130°C.